

ACKNOWLEDGEMENT RECEIPT

Electronic Version 1.1

Stylesheet Version v1.1.1

Title of Invention

Method of Forming Silicon Dioxide Using Siloxane

Submission Type : Information Disclosure
Statement

Application Number:

10/782094



EFS ID:

75168

Server Response:

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ISVR1	Submission was successfully submitted - Even if Informational or Warning Messages appear below, please do not resubmit this application
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First Named Applicant:

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Attorney Docket Number:

SAM-0483

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File Listing:

Doc. Name	File Name	Size (Bytes)	Date Produced (yyyymmdd)
us-ids	SamsungFourEightyThree-usldst.xml	1755	2005-01-03
us-ids	us-ids.dtd	7763	2005-01-03
us-ids	us-ids.xml	12026	2005-01-03
package-data	SamsungFourEightyThree-pkda.xml	2041	2005-01-03
package-data	package-data.dtd	27025	2005-01-03
package-data	us-package-data.xml	19263	2005-01-03
Total files size		69873	

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